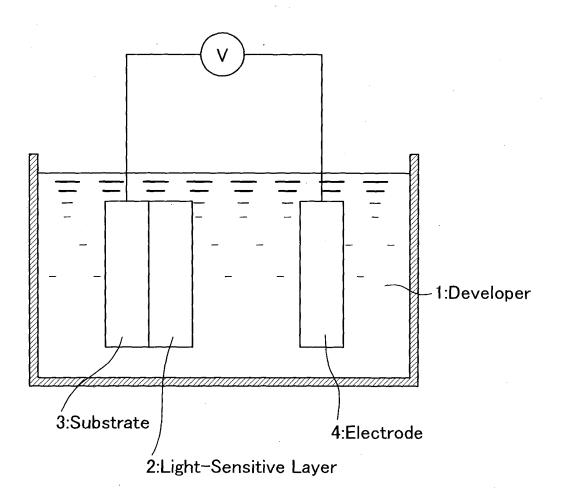
TITLE: DEVELOPER FOR PHOTOPOLYMERIZABLE PRESEN-SITIZED PLATE FOR USE IN MAKING LITHOGRAPHIC ETC.

INVENTOR(S): HIROYUKI NAGASE ET AL. DOCKET NO: 018995-735

SHEET 1 of 4

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FIG.1



TITLE: DEVELOPER FOR PHOTOPOLYMERIZABLE PRESENSITIZED PLATE FOR USE IN MAKING LITHOGRAPHIC ETC.

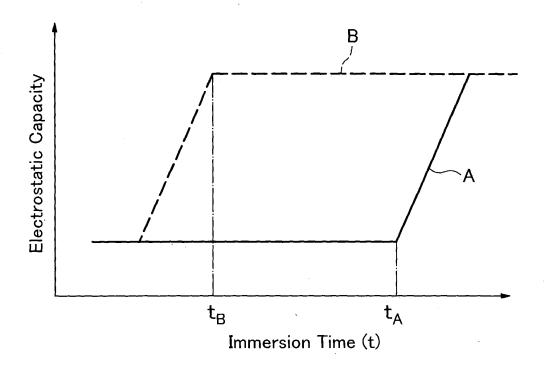
INVENTOR(S): HIROYUKI NAGASE ET AL.

DOCKET NO: 018995-735

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FIG.2



A: Light-Sensitive Layer Less Susceptible to Developer-Penetration

B: Light-Sensitive Layer Susceptible to Developer-Penetration

t_A: Time Elapsed Till the Electrostatic Capacity Undergoes a Change

t_B: Time Elapsed Till the Electrostatic Capacity Undergoes a Change

TITLE: DEVELOPER FOR PHOTOPOLYMERIZABLE PRESENSITIZED PLATE FOR USE IN MAKING LITHOGRAPHIC ETC.

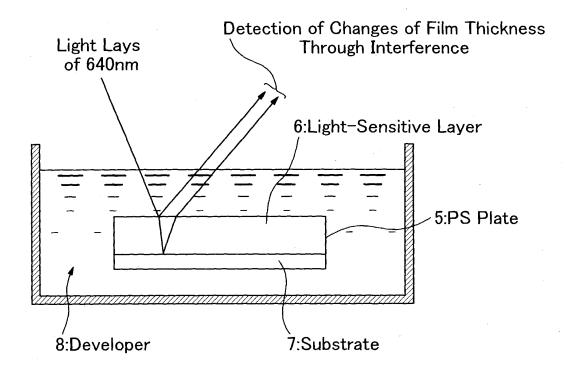
INVENTOR(S): HIROYUKI NAGASE ET AL.

DOCKET NO: 018995-735

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FIG.3



TITLE: DEVELOPER FOR PHOTOPOLYMERIZABLE PRESENSITIZED PLATE FOR USE IN MAKING LITHOGRAPHIC ETC.

INVENTOR(S): HIROYUKI NAGASE ET AL.

DOCKET NO: 018995-735

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FIG.4A

In Case of the Invention

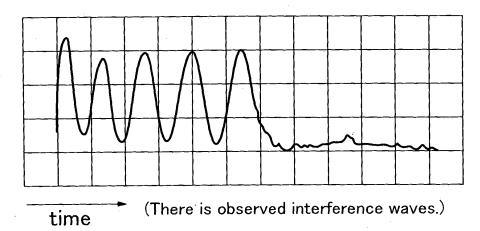
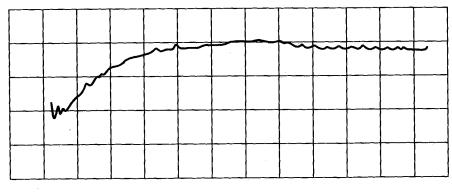


FIG.4B

In Case of the Conventional Technique



time (There is not observed any interference waves.)